

ECE 342

Electronic Circuits

Lecture 8

MOSFET Small Signal Model

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Biasing of MOS Transistors

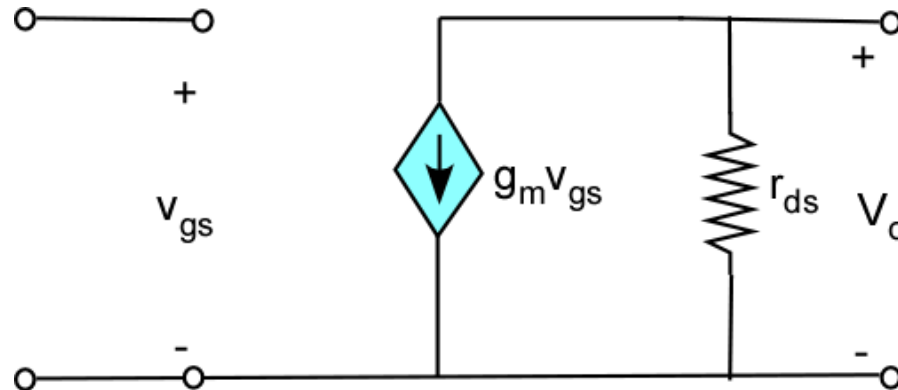
- **Bias Characteristics**

- Operation in saturation region
- Stable and predictable drain current

$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_T)^2$$

Common Source MOSFET Amplifier

Small-Signal Equivalent Circuit for MOS (device only)



$$I_D = \frac{1}{2} k_n' \frac{W}{L} (V_{GS} - V_T)^2$$

$$g_m = \left. \frac{\partial I_D}{\partial V_{GS}} \right|_{V_{GS}=V_{GSQ}} = \frac{2I_D}{V_{eff}}$$

where $V_{GS} - V_T = V_{eff}$

Which leads to

$$g_m = \sqrt{2k_n'} \sqrt{W/L} \sqrt{I_D}$$

g_m is proportional to $= \sqrt{W/L}$

MOSFET Output Impedance

To calculate r_{ds} , account for λ

$$r_{ds} = \left. \frac{\partial V_{DS}}{\partial I_D} \right|_{V_{GS}=V_{GSQ}} = \frac{1}{\lambda \mu \frac{W}{2L} C_{ox} [V_{GS} - V_T]^2} = \frac{1}{\lambda I_{DP}}$$

$$I_{DP} = \frac{1}{2} k'_n \frac{W}{L} (V_{GS} - V_T)^2$$

$$r_{ds} = \frac{V_A}{I_D}$$

r_{ds} , accounts for channel width modulation resistance.

Body Effect

- **The body effect**

- V_T varies with bias between source and body
- Leads to modulation of V_T

Potential on substrate affects threshold voltage

$$V_T(V_{SB}) = V_{T0} + \gamma \left[\left(2|\phi_F| + V_{SB} \right)^{1/2} - \left(2|\phi_F| \right)^{1/2} \right]$$

$$|\phi_F| = \left(\frac{kT}{q} \right) \ln \left(\frac{N_a}{n_i} \right) \quad \text{Fermi potential of material}$$

$$\gamma = \frac{\left(2qN_a \epsilon_s \right)^{1/2}}{C_{ox}} \quad \text{Body bias coefficient}$$

Body Effect – (Con't)

Define g_{mb} as the body transconductance

$$g_{mb} = \left. \frac{\partial I_D}{\partial V_{BS}} \right|_{\substack{V_{GS} = \text{constant} \\ V_{DS} = \text{constant}}}$$

Can show that $g_{mb} = \chi g_m$

$$\text{where } \chi = \frac{\partial V_T}{\partial V_{SB}} = \frac{\gamma}{2\sqrt{\phi_F + V_{SB}}}$$